IN THE CLAIMS:

1. (Original) In a method for forming a porous silica film using a hydrolyzable alkoxysilane compound, water, an alcohol and a surfactant <u>and acidic or alkaline catalyst</u>, the method for forming a porous silica film, which comprises using comprising:

acid hydrolysis or alkaline hydrolysis of the hydrolysable alkoxysilane compound,
utilizing one or more kinds of nonionic surfactant(s) having a 0.1 weight %
concentration according to the Du Nouy method expression and a surface tension of 45
mN/m or larger at 25°C as the surfactant,

coating a mixed solution obtained by mixing the nonionic surfactant, the alkoxysilane compound, water and the alcohol on a substrate,

and decomposing or burning out the surfactant in the mixed solution, and wherein said hydrolyzable alkoxysilane compound is from 0.05 to 0.5 mole of a dimethyldialkoxysilane compound represented by Si(CH₃)₂ (OR)₂ where a substituent R denotes a methyl group or an ethyl group.

2. (Currently Amended) The method for forming a porous silica film according to claim 1, wherein the nonionic surfactant comprises a polyoxyethylene-polyoxypropyl-ene condensate represented by [Chemical formula 1] $OH(CH_2CH_2O)x(CH(CH_3)CH_2O)y(CH_2CH_2O)xH \text{ where [Chemical formula 1](In a rational formula [Chemical formula 1], x and y denote an integer satisfying <math>1 \le x \le 185$ and $5 \le y \le 70$, respectively.) respectively.

3. (Currently Amended) The method for forming a porous silica film according to claim 2, wherein a mixing ratio in the mixed solution is 8 to 50 mole of the water, and 0.1 to 0.5 mole of the polyoxyethylene-polyoxypropylene condensate represented by OH(CH₂CH₂O)x(CH(CH₃)CH₂O)y(CH₂CH₂O)xH [Chemical formula 1] relative to 1 mole of the alkoxysilane compound.

4. (Canceled)

- 5. (Currently Amended) The method for forming a porous silica film according to any one of claims 1 to 3 [[4]], wherein a mixed surfactant obtained by mixing a cationic or nonionic surfactant into the nonionic surfactant is used as the surfactant.
- 6. (Currently Amended) The method for forming a porous silica film according to any one of claims 1 to 3 [[4]], wherein a worm-hole porous structure can be observed by a sectional transmission electron microscope in a silica film formed by decomposition or burning out the surfactant.
- 7. (Original) The method for forming a porous silica film according to claim 5, wherein a worm-hole porous structure can be observed by a sectional transmission electron microscope in a silica film formed by decomposition or burning out the surfactant.